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L Number	Hits	Search Text	l DB	Time stamp
1	149	<u> </u>	USPAT	2002/05/16 18:25
-		(CF4 or tetrafluoromethane) and (O2 or		
		oxygen)		
2	149	((("TiN") or (titanium adj nitride)) and	USPAT	2002/05/16 18:07
		(CF4 or tetrafluoromethane) and (O2 or oxygen)) and (etch\$3 or pattern\$3 or		
i i		defin\$3 or form\$3)		
3	140	((("TiN") or (titanium adj nitride)) and	USPAT	2002/05/16 18:08
		(CF4 or tetrafluoromethane) and (O2 or		
		oxygen)) and (etch\$3 or pattern\$3 or	1	0
	225	defin\$3)	II.CDAM	2002/05/16 18:08
4	235	(("TiN") or (titanium adj nitride) or barrier or etch\$1stop) and (CF4 or	USPAT	2002/05/16 18:08
		tetrafluoromethane) and (O2 or oxygen)		
5	219	((("TiN") or (titanium adj nitride) or	USPAT	2002/05/16 18:08
1		barrier or etch\$1stop) and (CF4 or		
		tetrafluoromethane) and (O2 or oxygen))		
6	45	and (etch\$3 or pattern\$3 or defin\$3) (titanium adj nitride) and (CF4 or	USPAT	2002/05/16 18:25
١٠	43	tetrafluoromethane) and (O2 or oxygen)	OSFAI	2002/03/10 10.23
7	1568	(titanium adj nitride) and (silicon adj	USPAT	2002/05/16 18:20
		carbide)		
8	126		USPAT	2002/05/16 18:21
9	9	carbide)) and (barrier adj layer) ((titanium adj nitride) and (silicon adj	USPAT	2002/05/16 18:24
	,	carbide)) and (etch\$1stop adj layer)	OSFAI	2002/03/10 10.24
10	51	(SiC or (Silicon adj carbide)) and (CF4 or	USPAT	2002/05/16 18:27
		tetrafluoromethane) and (O2 or oxygen)		
11	570	((SiC or (Silicon adj carbide))near\$4	USPAT	2002/05/16 18:28
		etch\$3) and (CF4 or tetrafluoromethane) and (O2 or oxygen)		
12	313	((SiC or (Silicon adj carbide))near\$4	USPAT	2002/05/16 18:30
		etch\$3) and (CF4 or tetrafluoromethane)		
		and (O2 or oxygen) and (ar or argon)		
13	916094	((SiC or (Silicon adj carbide))near\$4 etch\$3)	USPAT	2002/05/16 18:32
14	313	(((SiC or (Silicon adj carbide))near\$4	USPAT	2002/05/16 18:34
		etch\$3)) and (CF4 or tetrafluoromethane)		
		and (O2 or oxygen) and (ar or argon)		
15	37675	(SiC or (Silicon adj carbide))	USPAT	2002/05/16 18:42
16	916094	((SiC or (Silicon adj carbide))) near\$4	USPAT	2002/05/16 18:34
17	883749	((SiC or (Silicon adj carbide))) near\$2	USPAT	2002/05/16 18:34
		etch\$3		
18	312	(((SiC or (Silicon adj carbide))) near\$2	USPAT	2002/05/16 18:41
		etch\$3) and (CF4 or tetrafluoromethane) and (O2 or oxygen) and (ar or argon)		
19	239		USPAT	2002/05/16 18:36
		etch\$3) and (CF4 or tetrafluoromethane)		2002, 00, 10 20,00
		and (O2 or oxygen) and (ar or argon)) and		
20	27	substrate	HODE	0000/05/16 10 07
20	27	<pre>(((((SiC or (Silicon adj carbide))) near\$2 etch\$3) and (CF4 or tetrafluoromethane)</pre>	USPAT	2002/05/16 18:37
		and (O2 or oxygen) and (ar or argon)) and		
		substrate) and (SiC or (Silicon adj		
	400	carbide))		
21	108	(((SiC or (Silicon adj carbide))) near\$2 etch\$3) and (CH2f2 or difluoromethane) and	USPAT	2002/05/16 19:00
		(02 or oxygen) and (ar or argon)		
22	53		USPAT	2002/05/16 18:42
		etch\$3) and (CH2f2 or difluoromethane) and		
		(O2 or oxygen) and (ar or argon)) and substrate		
23	12		USPAT	2002/05/16 18:45
		etch\$3) and (CH2f2 or difluoromethane) and		= 102, 03, 10 10.45
		(O2 or oxygen) and (ar or argon)) and		
		substrate) and (SiC or (Silicon adj		
24	37675	carbide)) (SiC or (Silicon adj carbide))	USPAT	2002/05/16 18:45
	3,0,3	(010 of (011100)) adj carbide//	ANTWI	2002/03/10 10:43

25	14	((SiC or (Silicon adj carbide))) and	USPAT	2002/05/16 18:49
		(CH2f2 or difluoromethane) and (O2 or		
		oxygen) and (ar or argon)		
26	195	(CH2f2 or difluoromethane) and (O2 or	USPAT	2002/05/16 18:50
		oxygen) and (ar or argon) and (n2 or		
		nitrogen)		
27	37	((CH2f2 or difluoromethane) and (O2 or	USPAT	2002/05/16 18:51
		oxygen) and (ar or argon) and (n2 or		
		nitrogen)) and strip\$4		<u> </u>
28	10	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	USPAT	2002/05/16 18:59
		oxygen) and (ar or argon) and (n2 or		
		nitrogen)) and strip\$4) and (resist or		
		photo\$1resist or photo\$polymer)		
29	44499		USPAT	2002/05/16 19:00
		and strip\$4		
30	1142619		USPAT	2002/05/16 19:01
		near\$2 strip\$4		/ /
31	123		USPAT	2002/05/16 19:02
		photo\$polymer) near\$2 strip\$4) and (CH2f2		1
		or difluoromethane) and (O2 or oxygen) and		
1		(ar or argon)		
32	8066		USPAT	2002/05/16 19:01
		near2 strip\$4		
33	8		USPAT	2002/05/16 19:05
		photo\$polymer) near2 strip\$4) and (CH2f2		
		or difluoromethane) and (O2 or oxygen) and		1
	_	(ar or argon)		
34	5		USPAT	2002/05/16 19:06
		photo\$polymer) near2 strip\$4) and (CH2f2		
:		or difluoromethane) and (O2 or oxygen) and		
		(ar or argon) and (n2 or nitrogen)		